said etchant at the same pH as the pH of said etchant immediately before the addition of said oxidizer.

16. The method of Claim 10 wherein said liquid source of dissolved silicate ions is a colloidal suspension of silicon dioxide.

## REMARKS

Claims 4-9 have been rewritten in independent form as new claims 10-15 to include all of the limitations of claim 1, which was the base claim, which is in accordance with statement 5 under DETAILED ACTION of the above referenced Office Action. Claim 9 was further rewritten to clarify its original intent. Claim 2 has been rewritten, without the addition of new material as Claim 16, to depend upon claim 10.

For the above reasons, applicant submits that the claims are now in proper form, and that the claims define patentability over the prior art. Therefore, applicant submits that this application is now in condition for allowance, which action he respectfully solicits.

## **Conditional Request for Constructive Assistance**

Applicant has amended the claims of this application so that they are proper, definite, and define novel methods that are also unobvious. If for any reason this application is not believed to be in full condition for allowance, applicant respectfully requests the constructive assistance and suggestions of the Examiner pursuant to M.P.E.P. Section 2173.02 and Section 707.07(j) in order that the undersigned can place the application in allowable condition as soon as possible and without the need for further proceedings.

Very respectfully,

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Certificate of Mailing: I certify that on the date below this document will be deposited with the US Postal Service as first class mail in an envelope addressed to: "BOX NON-FEE AMENDMENTS, COMMISSIONER FOR PATENTS, WASHINGTON DC 20231.

2004 SEP 20 Lon Geist, Applicant